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TRANSMITTAL OF INFORMATION DISCLOSURE STATEMENT Docket No. (Under 37 CFR 1.97(b) or 1.97(c)) BUR920040086US1 In Re Application Of: Rankin et al. Customer No. Group Art Unit Confirmation No. Application No. Examiner Filing Date 024241 10/710602 07/23/04 Unassigned Title: METHOD TO SELECTIVELY CORRECT CRITICAL DIMENSION ERRORS IN THE SEMICONDUCTOR Address to: **Commissioner for Patents** P.O. Box 1450 Alexandria, VA 22313-1450 37 CFR 1.97(b) The Information Disclosure Statement submitted herewith is being filed within three months of the filing of a national application other than a continued prosecution application under 37 CFR 1.53(d); within three months of the date of entry of the national stage as set forth in 37 CFR 1.491 in an international application; before the mailing of a first Office Action on the merits, or before the mailing of a first Office Action after the filing of a request for continued examination under 37 CFR 1.114. 37 CFR 1.97(c) The Information Disclosure Statement submitted herewith is being filed after the period specified in 37 CFR 1.97(b), provided that the Information Disclosure Statement is filed before the mailing date of a Final Action under 37 CFR 1.113, a Notice of Allowance under 37 CFR 1.311, or an Action that otherwise closes prosecution in the application, and is accompanied by one of: ☐ the statement specified in 37 CFR 1.97(e); OR ☐ the fee set forth in 37 CFR 1.17(p).

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I certify that this document and authorization to charge deposit account is being facsimile transmitted to the United States  Patent and Trademark Office (Fax. No.  I certify that this document and fee is being deposited on with the U.S. Postal Service as first class mail under 37 C.F.R. 1.8 and is addressed to the													
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   William D. Sabo, Esc	a.												
Reg. No.: 27,465	•												
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Essex Junction, VT 05452													
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cc.													



## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE PATENT APPLICATION

Applicant:

Rankin et al.

Serial No.: 10/710602

Filed:

07/23/2004

Atty. Docket: BUR920040086US1

Title:

METHOD TO SELECTIVELY CORRECT CRITICAL DIMENSION ERRORS

IN THE SEMICONDUCTOR INDUSTRY.

## SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT UNDER 37 CFR 1.56, 1.97, 1.98

Honorable Commissioner of Patents and Trademarks Washington, D. C. 20231

Sir:

Applicants submit herewith form PTO-1449, listing patents, publications, or other information of which they are aware which they believe may be material to patentability pursuant to 37 CFR 1.56(b), and in respect of which there may be a duty to disclose under 37 CFR 1.56(a), together with legible copies of the patents, publications, or other information listed.

While the items submitted with this Information Disclosure Statement may be material to patentability pursuant to 37 CFR 1.56, in accordance with 37 CFR 1.97(h) it shall not be construed to be an admission that any patent, publication, or other information cited is "prior art" or is material to patentability for this invention unless specifically designated as such. In accordance with 37 CFR 1.97(g), the filing of this Information Disclosure Statement shall not be construed to mean that a search has been made or that no other information material to patentability, as defined in 37 CFR 1.56(b), exists.

Respectfully submitted,

Date: <u>Au6. 5, 20</u>04

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Attorney for Applicants **IBM Corporation** 

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				Docket Number (Optional) BUR920040086	Docket Number (Optional) BUR920040086US1			Application Number 10/710602				
INFORMATION DISCLOSURE CITATION  (Use several sheets if necessary)				Applicant(s) Rankin et a	Applicant(s) Rankin et al.							
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	V	Chung et al., DEEP-SUBMICROMETER MOS DEVICE FABRICATION USING A PHOTORESIST-ASHING TECHNIQUE, IEEE Electron Device Letters, Vol. 9, No. 4, April 1988, pages 186-188.										
		Chiong et al., CONTRAST ENHANCEMENT OF RESIST IMAGES BY SURFACE CROSSLINKAGE, IBM Technical Disclosure Bulletin, Vol. 31, No. 3, August 1988, page 349.										
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